Date submitted(M/D/Y): 　　 / /

**Application for I2CNER Common Equipment**

**I2CNER共通機器利用申請書**

**【１．Personal information / 個人情報】**

|  |  |
| --- | --- |
| Division / 部門 |  |
| よみがな |  |
| Name / 氏名 |  |
| Title / 職名 |  |
| Grade / 学年  \* Students are required to fill in |  |
| Group leader / ｸﾞﾙｰﾌﾟﾘｰﾀﾞｰ |  |
| Phone# / 電話番号 |  |
| E-mail |  |
| PW |  |

**【２．Equipment you want to use / 利用希望装置】**

\* Please visit the following URL then confirm information requested below. http://i2cner.kyushu-u.ac.jp/equipment/

|  |  |  |  |  |  |
| --- | --- | --- | --- | --- | --- |
| Use | ID | Equipment name  装置名 | Location  設置場所 | Trainer  (Faculty/教員 or PD)  \*All users are required to write trainers name regarding advanced equipment.  \*Student are required to write trainers name regarding each equipment.  \*Trainers are required to supervise student whom they trained. | |
| ○ | ←\*Please check for equipment to use. | |  | Ad: Advanced equipment | |
|  | 50 | 全自動X線回折システム/Automatic X-ray Diffraction System | Ⅱ-301(1) | Ad | \*Choose here |
|  | 51 | 酸素・窒素・水素分析装置/O2, H2, N2 ANALYZER | Ⅱ-301(3) |  | \*Choose here |
|  | 103 | 電界放出形走査電子顕微鏡SEM/Scanning Electron Microscope\_SEM | Ⅱ-301(3) | Ad | \*Choose here |
|  | 104 | 冷却断面加工装置/Cross section machining apparatus | Ⅱ-301(3) | Ad | \*Choose here |
|  | 57 | 膜抵抗測定ｼｽﾃﾑ,ｲﾝﾋﾟｰﾀﾞﾝｽｱﾅﾗｲｻﾞｰ/Film resistance measuring system | Ⅱ-301(1) | Ad | \*Choose here |
|  | 60 | ﾚｰｻﾞ回析式粒子径分布測定装置/Laser diffraction Particle Size Analyzer | Ⅱ-301(1) |  | \*Choose here |
|  | 61 | 走査型プローブ顕微鏡/Scanning Probe Microscope | Ⅱ-301(1) |  | \*Choose here |
|  | 62 | 高性能比表面積・細孔分布測定装置/Surface Characterization Analyzer | Ⅱ-301(1) |  | \*Choose here |
|  | 63 | ｺｰﾙﾄﾞｽﾌﾟﾚｰｲｵﾝ源搭載TOF-MSｼｽﾃﾑ/Cold-Spray Ionization TOF MS System | Ⅱ-301(1) | Ad | \*Choose here |
|  | 98 | 示差走査熱量計（DSC）/DIFFERENTIAL SCANNING CALORIMETRY | Ⅱ-301(1) | Ad | \*Choose here |
|  | 65 | 3D測定ﾚｰｻﾞｰ顕微鏡/3D Measuring Laser Microscope | Ⅱ-301(3) |  | \*Choose here |
|  | 105 | ﾏﾄﾘｸｽ支援ﾚｰｻﾞｰ脱離ｲｵﾝ化飛行時間型質量分析装置/Mass Spectrometry system | Ⅱ-301(1) |  | \*Choose here |
|  | 66 | 高圧ガス吸着量測定装置/High Pressure Isothermal Gas Adsorption Apparatus | Ⅱ-301(3) | Ad | \*Choose here |
|  | 67 | TG-DSC同時測定装置/Simultaneous Thermal Analysis Apparatus | Ⅱ-301(3) | Ad | \*Choose here |
|  | 55 | 分光蛍光光度計/SPECTROFLUOROPHOTOMETER | Ⅱ-301(3) |  | \*Choose here |
|  | 56 | 紫外可視近赤外吸収分光光度計/UV-VIS-NIR SPECTROPHOTOMETER | Ⅱ-301(3) |  | \*Choose here |
|  | 53 | ﾌｰﾘｴ変換赤外分光光度計,赤外顕微鏡/FT-IR, Automatic Infrared Macroscope | Ⅱ-301(3) |  | \*Choose here |
|  | 71 | 赤外顕微鏡/Nicolet iN10 MX FT-IR Imaging Microscope | Ⅱ-301(3) |  | \*Choose here |
|  | 69 | ＡｒクラスターイオンビームＸＰＳ/Ar Cluster Ion Beam XPS | Ⅱ-301(3) | Ad | \*Choose here |
|  | 73 | 超伝導核磁気共鳴装置NMR/Nuclear Magnetic Resonance (NMR) Spectroscopy System | Ⅱ-102 | Ad | \*Choose here |
|  | 92 | ナノインデンテーションテスタ（UNHT）/Ultra Nanoindentation Tester | Ⅱ-102 | Ad | \*Choose here |
|  | 94 | 卓上型放電プラズマ焼結機/Spark Plasma Sintering (SPS) Systems | Ⅱ-102 | Ad | \*Choose here |
|  | 52 | 高速ﾗﾏﾝｲﾒｰｼﾞﾝｸﾞ分光分析ｼｽﾃﾑ/Raman Imaging Spectrometer System | Ⅱ-301(3) |  | \*Choose here |
|  | 68 | ３元スパッタリング成膜装置/RF Plasma Sputtering Apparatus | Ⅱ-301(3) |  | \*Choose here |
|  | 72 | 2次イオン質量分析装置ＳＩＭＳ/Secondary Ion Mass Spectrometry(TOF-SIMS) | Ⅰ-101 | Ad | \*Choose here |
|  | 106 | ホール効果測定装置/Hall Effect Measurement System | Ⅱ-102 | Ad | \*Choose here |
|  | 93 | 表面エネルギー測定装置/Inverse Gas Chromatography | Ⅱ-102 | Ad | \*Choose here |
|  | 107 | ICP発光分光分析装置/ Inductively Coupled Plasma Optical Emission Spectrometer | Ⅱ-301(1) |  | \*Choose here |
|  | 78 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.1) | Ⅱ-404 |  | \*Choose here |
|  | 79 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.2) | Ⅱ-404 |  | \*Choose here |
|  | 80 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.9) | Ⅱ-404 |  | \*Choose here |
|  | 81 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.10) | Ⅱ-404 |  | \*Choose here |
|  | 82 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.3) | Ⅱ-404 |  | \*Choose here |
|  | 83 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.4) | Ⅱ-404 |  | \*Choose here |
|  | 85 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.8-1) | Ⅱ-404 |  | \*Choose here |
|  | 99 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.8-2) | Ⅱ-404 |  | \*Choose here |
|  | 100 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.8-3) | Ⅱ-404 |  | \*Choose here |
|  | 101 | ユニバーサル共通有機実験室/Common Organic L/Organic Hood (No.8-4) | Ⅱ-404 |  | \*Choose here |

**【３．Users of XRD or XPS / XRDまたはXPS利用者】**

\*Please check ☑ after confirmation / ご確認の上☑を入れてください。

|  |  |
| --- | --- |
| \*Check here | I have submitted "Experiment Plan" 実験計画書提出済。 |

**【４．Agreement form / 同意書】**

\*Please check ☑ after confirmation / ご確認の上☑を入れてください。

|  |  |
| --- | --- |
| \*Check here | I agree with the Rules for the use of Common equipment rooms and Equipment below.  私は下記I2CNER共通機器利用者規定に同意します。 |
| **Rules for the use of Common equipment rooms and Equipment**  **I2CNER共通機器利用者規程**   1. Only I2CNER members and their students are allowed to use I2CNER common equipment.   使用はI2CNER構成員及びその指導学生に限る。   1. Students can use under the supervision of I2CNER member   学生は構成員である指導教員の監督の下で使用することとする。   1. Be required to make a reservation on this system before use.   使用前に、本予約システムでの予約を行うこと。   1. Needs to record all required items on log book.   機器使用簿に必要事項を記載すること。   1. Shows your name and emergency contact number on a whiteboard when you leave a machine.   使用者が使用中にその場を離れる際は、使用者名と緊急連絡先（携帯番号等）をホワイトボードに記入のこと.   1. Please do not leave anything behind you, and clean up around the equipment.   出たゴミは必ず持ち帰り、機器の周りをきれいに清掃して退出のこと。   1. Participates in concerted cleaning of shared equipment room   共通機器部屋一斉清掃に参加のこと。   1. When errors are generated or consumables (gas etc.) are about to run out, please let a researcher in charge know.   エラーが出た場合や、消耗品（ガス残量等）がなくなりそうになった際は、装置担当者に連絡のこと。   1. When announcing a result in a publication obtained by the use of the equipment, the name of I2CNER should be mentioned as your affiliation, not as acknowledgement.I2CNER共通機器の成果を使って発表を行う際には、謝辞ではなく、所属にI2CNERの名前を入れること。 2. Required to take an "I²CNER Web Safety Training."   I²CNER Safety Trainingは必ず受けること。 | |

**【５．Written approval by responsible person / 責任者承諾書】**

\*Please check ☑ after confirmation / ご確認の上☑を入れてください。

|  |  |  |
| --- | --- | --- |
| \*Check here | I agree that user “　　　　　　　　 ”will use the I2CNER common equipment, and when there is a trouble such as breakdown due to improper operations etc…  I will take responsibility and repair it.  私は使用者“　　　　　　　　　”がI2CNER共通機器を使用することを承諾し、操作ミスなどによる故障等トラブルが有った際は、責任を持って対応・修理を行います。 | |
| Month/Day/Year　　年　　月　　日 | | Name of responsible person / 責任者氏名 |
|  | |  |